

**Corporate PR Contact**

John Doering
Molecular Imprints, Inc.
1-512-334-1202
jdoering@molecularimprints.com

Agency Contact

David Moreno
MCA
1-650-968-8900 ext. 125
dmoreno@mcapr.com

**SEMATECH PURCHASES IMPRINT LITHOGRAPHY SYSTEM FROM
MOLECULAR IMPRINTS FOR IC DEVELOPMENT AT THE 32NM NODE AND BELOW**

AUSTIN, TX. Feb 26, 2008 – Molecular Imprints, Inc. (MII) today announced that SEMATECH, one of the world's leading nanoelectronics consortia chartered with accelerating the commercialization of technology innovations into manufacturing solutions, has purchased MII's latest-generation semiconductor imprint lithography system—the Imprio[®] 300. The Imprio 300 will be delivered to SEMATECH at the College of Nanoscale Science and Engineering (CNSE) of the University at Albany in mid-2008 to support advanced lithography program activities.

The goal of SEMATECH and MII in this placement is to demonstrate the feasibility of MII's Step and Flash[®] Imprint Lithography (S-FIL[®]) technology for production applications at the 32nm node and below. Leveraged in MII's Imprio systems, S-FIL replicates the ultra-high resolution of e-beam lithography with the low cost of ownership (CoO) of dry optical lithography to provide a highly extendible manufacturing solution for multiple device generations. The first target of the collaborative partnership that will accompany this placement will be to demonstrate and enhance overlay performance, as well as identify development opportunities to accelerate the introduction of S-FIL into manufacturing.

“As we move to sub-32nm, the costs and challenges of extending the lithography roadmap continue to escalate,” said Michael Lercel, lithography director at SEMATECH. “One of SEMATECH's goals is to identify cost-effective and manufacturable technologies. Nanoimprint has demonstrated excellent resolution and image fidelity, so now is the time to evaluate its manufacturability. That is the goal of the SEMATECH program and our collaboration with Molecular Imprints.”

“The order of our latest-generation Imprio system by SEMATECH highlights growing semiconductor industry interest in our innovative nanoimprint technology,” said Mark Melliar-Smith, CEO of Molecular Imprints. “MII's S-FIL technology is ideally suited for patterning critical layers in sub-32nm devices, and we anticipate that successful prototyping at the 32nm node will lead to volume manufacturing adoption. We welcome this partnership with SEMATECH and its member companies, and believe that increasing industry investment in the imprint technology roadmap will accelerate its introduction into manufacturing.”

MII's S-FIL technology is built on the semiconductor industry's existing optical lithography infrastructure—using commercially available photomasks, exposure sources and resists—and is the only imprint lithography technology capable of meeting the overlay requirements of the semiconductor industry. As a result, MII's systems are a drop-in solution suitable for mix-and-match strategies in the semiconductor industry, where their resolution and cost advantages can be deployed on specific critical layers. MII's nanoimprint technology offers the promise of enabling lithography in the semiconductor industry by delivering the production environment overlay capabilities the industry requires, without sacrificing the demonstrated sub-10nm resolution capabilities of imprint lithography.

-more-



About Molecular Imprints, Inc.

Molecular Imprints, Inc. is the technology and market leader of high-resolution imprint systems for nano-patterning. The company has commercialized proprietary imprint lithography technologies (S-FIL[®] and Drop-on-Demand[™]) and demonstrated sub-10-nanometer resolution patterning capability. Molecular Imprints provides enabling lithography systems and technology for manufacturing applications in the areas of semiconductors, nano-devices, solid-state lighting, micro-optical components, and magnetic and solid-state data storage applications. For more information, visit www.molecularimprints.com.

###